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(54) Title (EN): STABLE THRESHOLD SWITCHING MATERIALS FOR SELECTORS OF RESISTIVE MEMORIES

(54) Title (FR): MATÉRIAUX DE COMMUTATION À SEUIL STABLE POUR SÉLECTEURS DE MÉMOIRES RÉSISTIVES

(57) Abstract:
(EN): A stable threshold switching material for selectors employed in resistive memories is provided. The material is amorphous and has a composition given by $(V, Nb)_{1-x}(Si, Hf, W)_xO_y$, where $0 < x < 1$ and y is within a range of 1.5 to 3.

(FR): La présente invention concerne un matériau de commutation à seuil stable pour des sélecteurs employés dans des mémoires résistives. Le matériau est amorphe et présente une composition fournie par $(V, Nb)_{1-x}(Si, Hf, W)_xO_y$ où $0 < x < 1$ et y est compris de la plage de 1,5 à 3.

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Declarations:

Declaration made as to the identity of the inventor (PCT Rules 4.17(i) and 51bis.1(a)(i))